

**IMMERSION LITHOGRAPHIC PROCESS USING A
CONFORMING IMMERSION MEDIUM**

ABSTRACT OF THE DISCLOSURE

5 A method of making a device using a lithographic system having a lens
from which an exposure pattern is emitted. A conforming immersion medium can
be positioned between a photo resist layer and the lens. The photo resist layer,
which can be disposed over a wafer, and the lens can be brought into intimate
contact with the conforming immersion medium. The photo resist can then be
exposed with the exposure pattern so that the exposure pattern traverses the
10 conforming immersion medium.

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